

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant	:	Hada et al.
Appl. No.	:	10/557,694
Filed	:	November 22, 2005
For	:	RESIN FOR PHOTORESIST COMPOSITION, PHOTORESIST COMPOSITION AND METIOD FOR FORMING RESIST PATTERN
Examiner	:	Eoff, A.
Group Art Unit	:	1795

AMENDMENT AND RESPONSE TO FINAL OFFICE ACTION

Mail Stop AF
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

In response to the final Office Action mailed **November 20, 2008**, please amend the above-referenced application as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks/Arguments begin on page 6 of this paper.